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TI Curable elastomer compositions for use in scanners of electron beam irradiation apparatus

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PA RKS Schrumpftechnik-Garnituren G.m.b.H., Fed. Rep. Ger.

SO Ger. Offen., 3 pp.

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DT Patent

LA German

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	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	DE---3735502	A1	19890503	1987DE-3735502	19871020
PRAI	1987DE-3735502		19871020		

AB The title compns., which, when cured, are unaffected by electron beams and remain flexible and skid-resistant, contain elastomers, partially cryst. materials, fillers, and antioxidants. Suitable polymers include C2H4-acrylate rubbers, EPR, EPDM, LLDPE, polyisobutylene, and EVA.

IT Rubber, ethylene-propene

RL: USES (Uses)

(electron beam-resistant, for scanners for electron beam app.)

IT Antioxidants

(for electron beam-resistant rubbers and polyolefins for scanners for electron beam app.)

IT Rubber, synthetic

RL: USES (Uses)

(Bu acrylate-ethylene, electron beam-resistant, for scanners for electron beam app.)

IT Rubber, synthetic

RL: USES (Uses)

(EPDM, electron beam-resistant, for scanners for electron beam app.)

IT Recording apparatus

(electron-beam, scanners for, rubber and polyolefin compns. for)

IT Rubber, synthetic

RL: USES (Uses)

(ethylene-Me acrylate, electron beam-resistant, for scanners for electron beam app.)

IT Rubber, synthetic

RL: USES (Uses)

(ethylene-vinyl acetate, electron beam-resistant, for scanners for electron beam app.)

IT Rubber, synthetic

RL: USES (Uses)

(isobutylene, electron beam-resistant Oppanol B100, for scanners for electron beam app.)

IT Alkenes, polymers

RL: USES (Uses)

(.alpha.-, polymers, with ethylene, electron beam-resistant, for scanners for electron beam app.)

IT 2082-79-3, Irganox 1076 10081-67-1, Naugard 445 26780-96-1

29117-01-9, Stabaxol P 70331-94-1, Naugard XL1

RL: USES (Uses)

(antioxidants, for electron beam-resistant polymers for scanners for electron beam app.)

IT 74-85-1D, Ethene, polymers with .alpha.-olefins

RL: USES (Uses)

(linear low-d., electron beam-resistant, for scanners for electron beam app.)

IT 74-85-1

RL: USES (Uses)

(rubber, EPDM, electron beam-resistant, for scanners for electron beam app.)

IT 9003-27-4, Polyisobutylene 9010-79-1 9010-86-0 24937-78-8, EVA  
25103-74-6, Ethylene-methyl acrylate copolymer 25750-84-9,  
Butylacrylate-ethylene copolymer  
RL: USES (Uses)  
(rubber, electron beam-resistant, for scanners for electron beam app.)